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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

HAGIWARA ET AL. Applicant(s):

Serial No.:

Filed:

For:

January 14, 2000
PHOTOSENSITIVE RESIN COMPOSITION

Aug 2000

PHOTOSENSITIVE RESIN COMPOSITION

Aug 2000

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Art Unit:

Examiner:

## **AMENDMENT**

**Assistant Commissioner for Patents** Washington, D.C. 20231

August 27, 2001

SIR:

In response to the Office Action mailed April 25, 2001, please amend the above-identified application as follows:

**IN THE CLAIMS:** 

Please cancel claims 20, 26, 27, 32 and 33 without prejudice or disclaimer, and amend the claims remaining in the application as follows: